Technique of Defining the Electric Resistance of the IC contact Pads

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Abstract – There are presented the technique and results of defining the electric resistance value of the IC microcontact connection contact pads.

Keywords - integral circuit, contact pad, resistance

The contact pad resistance may essentially influence the flexible IC microcontact connection (MCC) resistance. Due to the nonuniformity of the current line distribution under the contact pad (CP) lead, it is not easy to define its electric resistance $R_{\kappa n}$ [1, p127].

The CP resistance is given as a sum of two components:

$$R_{\kappa n n} = R_{\kappa n 1} + R_{\kappa n 2}, \tag{1}$$

where $R_{\kappa nl}$ is the resistance of the CP before-lead (by the current flow direction) area of length a, $R_{\kappa n2}$ is the resistance of the CP under-lead area of length l. It is found by experiment that the CP area of length c (Fig.1) does not influence its resistance essentially.

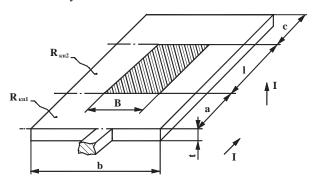


Fig.1. CP components determining its resistance: $R_{\kappa nI}$ is the resistance which is calculated by formula (2), $R_{\kappa n2}$ is the resistance defined by formulae (3)-(5). The area with a lead is cross-hatched; the arrows show the current flow direction.

The resistance $R_{\kappa nI}$ component is defined by the formula:

$$R_{\kappa n1} = \rho_2 \cdot a/b \cdot t, \qquad (2)$$

where ρ_2 is the CP resistivity, a is the CP before-lead area length by the current flow direction, b and t are the CP width and thickness, respectively.

The $R_{\kappa n2}$ component is found from the MCC resistance [2]:

$$R_{\kappa n2} = \frac{R_{\kappa n\partial}}{I + \frac{r_I}{r_2}}.$$
 (3)

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where $R_{\kappa n \partial}$ is the total resistance of the CP under-lead area and a deformed wire section and the CP.

Then, defining (1) the CP impedance is:

$$R_{\kappa n \bar{n}} = \frac{\rho_2 \cdot a}{b \cdot t} + \frac{R_{\kappa n \bar{o}}}{1 + \frac{r_1}{r_2}}.$$
 (4)

When defining the MCC resistance R_{κ} , it is proposed to use a more exact formula instead of the expression given in [3]:

$$R_K = \frac{r_1 + r_2}{\alpha \cdot th \, \alpha l},\tag{5}$$

where $\alpha = \sqrt{y(r_1 + r_2)}$, y is a linear conductance of the transition layer.

To define the resistance of multilayer contact pads there are used their resistivities given. Dependence of the resistance components of the paste 3713 CP on its dimensions with a contact area with a lead of 0.1x0.1 mm is shown in (Fig.2).

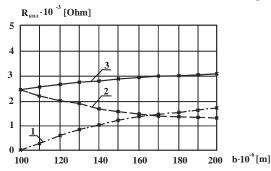


Fig.2. Change of the Resistance of the Paste 3713 CP components with the CP dimensions $(1-R_{\kappa n1}, 2-R_{\kappa n2}, 3-R_{\kappa nn})$.

The resistances of the 0.2×0.2 mm IC contact pads defined by this technique are: Al CP – $11.6 \cdot 10^{-3}$ Ohm, Al-Ni-Au CP - $16.2 \cdot 10^{-3}$ Ohm, paste 3713 CP – $3.1 \cdot 10^{-3}$ Ohm.

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